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PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE
(Case No. 98,162-B)

In re Application of:)

DeGendt, et al.)

Serial No.: 09/207,546)

Filed: December 8, 1998)

For: METHOD FOR REMOVING ORGANIC)
CONTAMINANTS FROM A)
A SEMICONDUCTOR SURFACE)

Group Art Unit: 1746

Examiner: Ahmed

Commissioner for Patents
Washington, D.C. 20231



AMENDMENT

Dear Sir:

In response to the outstanding Office Action mailed August 30, 2000, please enter the following remarks and amendments in the above-referenced patent application.

IN THE CLAIMS

Please cancel claims 1-26, 34 and 36-39 without prejudice. Please amend claim 29 as follows:

29. (Amended) A method for removing contaminants from a silicon substrate comprising the steps:

holding said substrate in a tank;

filling said tank with a fluid mixture comprising water, [and] ozone and an additive acting as a scavenger to thereby achieve an oxide growth on said substrate;

removing the oxide; and

drying the silicon wafer.

McDONNELL BOEHNNEN
HULBERT & BERGHOFF
300 South Wacker Drive, Suite 3200
Chicago, Illinois 60606
(312) 913-0001